

ABSTRACT

A projection exposure apparatus (100) has a substrate table (30) on which a substrate (W) is mounted that can be moved holding the substrate, a position measuring system (18 and others) that measures positional information of the substrate table, and a correction unit (19) that corrects positional deviation occurring in at least either the substrate or the substrate table due to supply of a liquid. In this case, the correction unit corrects the positional deviation occurring in at least either the substrate or the substrate table due to the supply of the liquid. Accordingly, exposure with high precision using a liquid immersion method is performed on the substrate.